

## Equipment with plasma sources for materials processing in ultra-high vacuum by magnetron sputtering and e-beam ATC 2200 AJA INTERNATIONAL

### **Application:**

Obtaining thin conductive materials and nanostructures, materials resistance, oxidic semiconductors, insulators.

Functional parameters:

- pressure min.  $5 \times 10^{-8}$  torr;
- working pressure in evaporation,  $5 \times 10^{-8}$  torr;
- vacuum system:  $760 - 5 \times 10^{-9}$  torr;
- 4 spray source in CC, CC pulse and Radio Frequency;
- electron beam evaporator with ultra-high vacuum (UHV) and 5 crucibles.

